

Abstract of the Disclosure

Provided is a high-speed electron beam lithography system including a transfer chamber; a plurality of electron beam lithography chambers, each of which is connected to the transfer chamber and includes a multicolumn portion; and input and output loadlock chambers, each of which is connected to the transfer chamber. Herein, the plurality of electron beam lithography chambers and the input and output loadlock chambers are connected to the transfer chamber, forming a cluster. Also, a plurality of wafers are respectively loaded into the plurality of electron beam lithography chambers so as to drive the electron beam lithography chambers at the same time.